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Applicant also respectfully reserves the right to later set forth how the instant invention is distinguished over the disclosure of any document or other art, including the disclosure of those documents discussed herein, that may be cited by the Examiner in rejecting a claim in the instant patent application.

As a RCE was filed no fee is believed necessary. If a fee is required, please charge Deposit Account No. 50/1039.

Respectfully submitted,



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LIST OF PUBLICATIONS CITED BY APPLICANT	<u>Atty Docket No.</u> SEL 239	<u>Serial No.</u> 09/782,239
	<u>Applicant</u> Toshimitsu KONUMA et al	
	<u>Filing Date</u> February 13, 2001	<u>Group</u> 2814

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE
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	EP 0 893 485	01/27/99	Sumitomo Chem Co.			07/22/98
	EP 0 899 987	03/03/99	TDK Corp.			08/28/98

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

(Include name of author (in CAPITAL LETTERS), title of article or item (book, magazine, journal, serial, symposium, catalog, etc.) date, pages(s), volume-issue number(s), publisher, city and/or country where published).

- 1) European Search Report re application no. EP 03 02 0964, mailed December 3, 2003.
- 2) FRITSCH, U. et al, "A Submicron CMOS Two Level Metal Process with Planarization Techniques," V-MIC Conf., June 13-14, 1988 IEEE, pp. 69-75 (1988).
- 3) IBARAKI, N. et al, "A New a-Si TFT with SiO₂/SiN_x Gate Insulator for 10.4 inch LCDs," Proceedings of the International Display Research Conference, IEEE, pp. 97-100, (1991).
- 4) PRAMANIK, D. et al, "A High Reliability Triple Metal Process for High Performance Application Specific Circuits," VLSI Multilevel Interconnection Conference, June 11-12, 1991, pp. 27-33, (1991).

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*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP form. Draw line through citation if not in conformance and not considered. Include a copy of this form with the next communication to applicant.